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Applicant
Alan Wong et al.Filing Date
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U.S. Patent Documents

Examiner Initial	Desig. ID	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						

Foreign Patent Documents or Published Foreign Patent Applications

Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AB							

Other Documents (include Author, Title, Date, and Place of Publication)

Examiner Initial	Desig. ID	Document
DCM	AC	International Technology Roadmap for Semiconductors 2000 Update, "Metrology", pages 1-12.
	AD	International Technology Roadmap for Semiconductors 2000 Update, "Overall Roadmap Technology Characteristics", pages 1-32.
	AE	International Technology Roadmap for Semiconductors 1999 Edition, "Metrology", pages 295-313.
	AF	International Technology Roadmap for Semiconductors 1999 Edition, "Introduction", pages 1-22.
	AG	International Technology Roadmap for Semiconductors 1999 Edition, "Overall Roadmap Technology Characteristics and Glossary", pages 1-22.
	AH	International Technology Roadmap for Semiconductors, "On-Line ITRS Documents", 3 pages: http://public.itrs.net/Reports.htm , last updated June 4, 2001 (printed 10/26/2001), http://public.itrs.net/Files/2000UpdateFinal/2kUdFinal.htm , last updated December 15, 2000 (printed 10/26/2001), http://public.itrs.net/Files/1999_SIA_Roadmap/Home.htm , (printed 10/26/2001).
	AI	"EEEL, OMP, Optical-Based Dimensional Metrology", 8 pages, http://www.eeel.nist.gov/omp/dimension_optical.html , dated June 12, 2001 (printed 10/22/2001).
	AJ	"EEEL, OMP, Critical Dimension and Overlay Metrology Program", 1 page, http://www.eeel.nist.gov/omp/dimension.html , dated June 12, 2001 (printed 10/22/2001).
	AK	"Nanotechnology", 8 pages, http://www.eeel.nist.gov/812/nano.html , (printed 10/22/2001).
	AL	"EEEL, OMP, Electrical-Based Dimensional Metrology", 7 pages, http://www.eeel.nist.gov/810.01/dimension_electrical.html , dated June 12, 2002 (printed 10/22/2001).
	AM	"The Fundamentals of Overlay Metrology", 4 pages, http://www.e-insite.net/semiconductor/index.asp?layout=articlePrint&articleID=CA159008 , dated 9/1/2002 (printed 01/21/2002).
	AN	International Technology Roadmap for Semiconductors 2001 Edition, "Executive Summary", pages 1-57.
	AO	International Technology Roadmap for Semiconductors 2001 Edition, "Metrology", pages 1-24.
	AP	"2001 ITRS Home Page", 2 pages, http://public.itrs.net/Files/2001ITRS/Home.htm , (printed 01/21/2002).
	AQ	"The Fundamentals of Overlay Metrology - SI September 2001", 6 pages, http://www.google.com/search?q=cache:ofSQhAFmV6UC:209.67.253.149/semiconductor , (printed 01/21/2002).

Examiner Signature

DAVID C. MEYER

Date Considered

9/3/03

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